SYNOPSYS

CATS is the industry leading platform for mask data preparation (MDP) that has been enabling semiconductor photomask manufacturing for decades. CATS MDP provides a comprehensive solution that performs mask fracture, mask error correction, mask rule checking, and a graphical and job view debugging platform. The CATS platform features industry leading performance, scalability on thousands of cores, and tight integration into the Synopsys Proteus Platform.

CATS Mask
Rule Checking

Applications

CATS Mask Rule Checking features industry leading SmartMRC, whose native curvilinear engine provides unprecedented accuracy and runtime. SmartMRC features unique curvilinear commands and interface to accurately define and check complex curvilinear designs.

CATS Mask Error Correction leverages Synopsys leading OPC correction and modeling technology to provide a model-based approach to compensating for mask writing discrepancies. Highest accuracy is achieved with a native curvilinear correction engine, and tight integration into the Proteus Platform.

CATS Fracture features industry leading performance and supports all major mask writer formats for MEBES, Laser Write, Variable Shaped Beam (VSB), and Multibeam Mask Writers (MBMW). The Synopsys Proteus CATS Exchange (PCX) can enable fracture to complete minutes of correction.

Features:

- Supports manhattan and curvilinear inputs and output
- Jobdeck graphical viewing and editing
- CD Metrology and Inspection support
- CATS Mask Error Correction technology provides a model-based approach to compensate for mask writing discrepancies
- Manhattan and curvilinear checking with market leading SmartMRC
- Integration into the Proteus OPC platform
- Defect avoidance capabilities
- Scalable distributed processing on thousands of cores

For more information please contact your local sales representative or email us at manufacturing@synopsys.com